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PATENT APPLICATION  
Do. No. 4234-8

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Dong-Ho KIM et al.

Serial No. 09/693,409

Examiner: D. Rutledge

Filed: October 19, 2000

Group Art Unit: 2851

For: SEMICONDUCTOR MANUFACTURING APPARATUS FOR  
PHOTOLITHOGRAPHIC PROCESS

**Box Non-Fee Amendment**

Assistant Commissioner for Patents  
Washington, D.C. 20231

*B# / pmc / A*  
*3/9/cr*  
*RLBm*

**RESPONSE TO OFFICE ACTION**

Responsive to the Office Action, dated October 17, 2001, please amend the application as follows.

**IN THE CLAIMS**

Please amend the claims as follows:

- a 1*
1. (Once amended) A semiconductor manufacturing apparatus for a photolithographic process including a coating process and a developing process, the apparatus comprising:
    - a first port where a substrate comes in and goes out;
    - a second port, having a constant distance from the first port, where the substrate comes in and goes out;
    - coating means for performing the coating process; and
    - developing means for performing the developing process, the developing means being stacked in parallel with the coating means,wherein the coating means includes: